

REMARKS

The rejection of Claims 9-24 under 35 U.S.C. § 103(a) as unpatentable over U.S. 6,832,036 (Ghoshal et al) is respectfully traversed.

As recited in sole independent Claim 9 herein, the invention is:

An optical waveguide formed from an optical waveguide-forming material, said optical waveguide-forming material comprising a photocurable organopolysiloxane composition comprising an alkali-soluble organopolysiloxane and a photoacid generator,

said organopolysiloxane possessing hydroxyl groups resulting from ring-opening of some or all of epoxides, and being obtained by (co)hydrolytic condensation of at least one silane compound having the formula (1):



wherein R^1 is a monovalent organo group of 2 to 30 carbon atoms having hydrolyzable epoxide, and R^2 is hydrogen or a substituted or unsubstituted monovalent hydrocarbon group of 1 to 10 carbon atoms, and having an average molecular weight of 500 to 50,000 as determined by GPC using polystyrene standards,

wherein said (co)hydrolytic condensation comprises carrying out (co)hydrolysis in the presence of an acid catalyst, thereby forming a (co)hydrolyzate, and then subjecting the (co)hydrolyzate to polycondensation, while alcohol formed and any solvent present is distilled off by heating, thereby yielding a (co)hydrolytic condensate having silanol groups.

(Emphasis added.)

While Ghoshal et al discloses optical waveguide structures containing siloxane resin compositions, having structural units X and optionally structural units Y therein, which structural units X contain functional groups that may contain terminal epoxy groups, Ghoshal et al neither discloses nor suggests ring opening some or all of the epoxy groups to form hydroxyl groups, nor the presence of silanol groups.

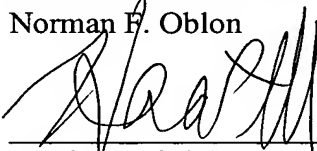
In addition, **submitted herewith** is a certified English translation of priority application Japan 2002-209388, filed July 18, 2002, which date is before the U.S. filing date of October 11, 2002 of Ghoshal et al.

For the above reasons, it is respectfully requested that the rejection over Ghoshal et al be withdrawn.

All of the presently-pending claims in this application are now believed to be in immediate condition for allowance. Accordingly, the Examiner has respectfully requested to pass this application to issue.

Respectfully submitted,

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